

What is claimed is:

- 1 1. A noise reduction device comprising:
 2 a complementary metal-oxide semiconductor (CMOS) transistor operable as a
 3 two-terminal device in a depletion mode and having a non-linear voltage variation for
 4 charge being removed at a constant rate, the CMOS transistor is formed in an n-type
 5 substrate having an n-type drain, an n-type source, an p-type polysilicon gate, and a gate
 6 oxide layer.

- 1 2. The noise reduction device of claim 1, wherein the non-linear voltage variation is
 2 given by:

$$v_2(t) = V_{cc} - \frac{aCo}{K} - \sqrt{\left(\frac{aCo}{K}\right)^2 - \frac{2It}{K}}$$

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- 1 3. The noise reduction device of claim 2, wherein the gate oxide layer has a
 2 thickness of between about twenty and forty angstroms.

- 1 4. A circuit comprising:
 2 a voltage node;
 3 a ground node; and
 4 a transistor coupled between the voltage node and the ground node, the transistor
 5 including an p-type polysilicon gate is capable of decreasing noise signals above an
 6 absolute value of an operating voltage value at the voltage node and increasing noise
 7 signals below the absolute value of the operating voltage value. (1)

- 1 5. The circuit of claim 4, wherein the operating voltage value is between about .5
 2 volts and about 1.5 volts.

- 1 6. The circuit of claim 5, further comprising:
2 a logic cell coupled to the voltage node and located in close proximity to the
3 transistor.
- 1 7. A circuit comprising:
2 an energy source;
3 a processor having a plurality of nodes coupled to the energy source and forming
4 a power supply grid having a number of resonant frequencies; and
5 a number of transistors coupled to at least one of the plurality of nodes such that
6 at least one of the number of transistors is operable as a voltage variable capacitor capable
7 of reducing the amplitude of resonant frequencies.
- 1 8. The circuit of claim 7, wherein the number of transistors is greater than about ten
2 thousand.
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- 1 9. A circuit comprising:
2 a die having a high voltage node and a low voltage node; and
3 a transistor coupled between the high voltage node and the low voltage node and
4 operable for controlling a voltage at the low voltage node.
- 1 10. The circuit of claim 9, wherein the transistor has a gate, a drain, and a source, and
2 the gate is coupled to the high voltage node and the source and the drain are coupled to
3 the low voltage node.
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- 1 11. A circuit comprising:
2 a substrate;
3 a load fabricated on the substrate;
4 an energy source coupled to the load, the energy source having an operating
5 voltage and a unidirectional noise signal; and

6 an electronic device fabricated on the substrate and coupled to the load, the
7 electronic device is capable of reducing the unidirectional noise signal more than a fixed
8 capacitor having a capacitance value equal to the capacitance value of the electronic
9 device operating at the operating voltage.

1 12. The circuit of claim 11, wherein the electronic device is a voltage variable
2 capacitor.

1 13. The circuit of claim 11, wherein the electronic device is a MOSFET.

1 14. A circuit comprising:
2 a die;
3 a ground node located on the die;
4 a voltage node located on the die; and
5 an electronic device coupled between the ground node and the voltage node and
6 capable of providing an asymmetrical response to incremental voltage variations about an
7 operational node voltage at the voltage node.

1 15. The circuit of claim 14, wherein incremental voltage variations of one polarity
2 are damped and incremental voltage variations of the opposite polarity are amplified.

1 16. The circuit of claim 14, wherein the bias node voltage is about 1.3 volts.

1 17. An integrated circuit comprising:
2 a die;
3 a processor having a plurality of cells formed on the die; and
4 a number of electronic devices coupled to at least one of the plurality of cells and
5 capable of damping positive voltage variations at the cell and amplifying negative voltage
6 variations at the cell.

1 18. The integrated circuit of claim 17, wherein the plurality of cells are fabricated
2 using a complementary metal-oxide semiconductor manufacturing process.

1 19. A method comprising:
2 receiving an energy signal having a noise component at a cell formed on a die;
3 and
4 filtering the energy signal to form a filtered energy signal by decoupling the cell
5 with a voltage variable capacitor.

1 20. The method of claim 19, wherein receiving an energy signal having a noise
2 component at a cell comprises:
3 receiving a power supply signal at the cell.

1 21. The method of claim 19, wherein filtering the energy signal to form a filtered
2 energy signal by decoupling the cell with a voltage variable capacitor comprises:
3 filtering the energy signal with at least one-hundred CMOS transistors operating
4 in the depletion-accumulation region.

1 22. The method of claim 19, further comprising:
2 configuring at least one of the number of electronic devices to have a drain, a
3 source, and a bulk connection coupled to a high voltage level and a gate coupled to a low
4 voltage level.

1 23. A method comprising:
2 adding a number of electronic devices having a voltage variable capacitance to an
3 electronic grid to suppress resonant frequencies in the electronic grid.

1 24. The method of claim 23, wherein adding a number of electronic devices
2 comprises:
3 selecting an active electronic device; and

4 coupling the active electronic device between a high voltage level and a low
5 voltage level at a logic cell.

1 25. The method of claim 23, further comprising:
2 locating at least one of the number of electronic devices between a logic cell and a
3 decoupling capacitor.

1 26. A method comprising:
2 transforming a resonant frequency on a power supply grid network resonant at the
3 resonant frequency to a higher frequency.

1 27. The method of claim 26, wherein transforming a resonant frequency on a power
2 supply grid network resonant at the resonant frequency to a higher frequency comprises:
3 adding a voltage variable capacitor to the power supply grid network.

1 28. The method of claim 27, further comprising:
2 adding a plurality of CMOS transistors configured to operate in the depletion-
3 accumulation region to the power supply grid network.